

ACS-300

Advanced Control System

ACS-300

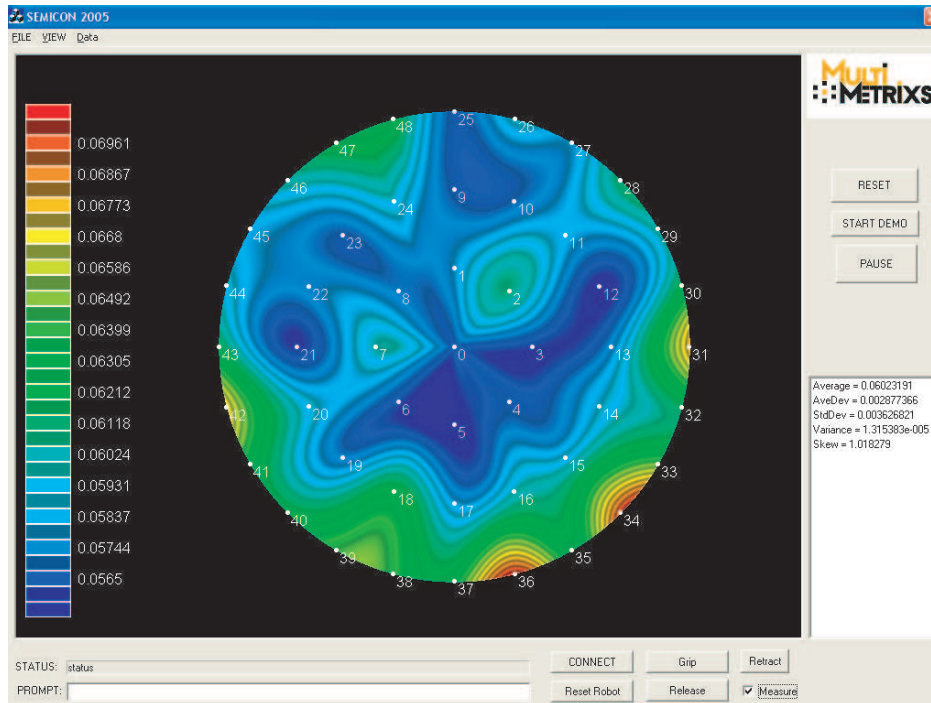
System Specification

Measurement spot size	4 mm ²
Number of spots measured	1-127*
Measurable range (resistance (Ω /sq))	0.001 - 50
Resistivity Range ($\Omega \times \text{cm}$)	0.001 – 1,000
Accuracy (resistance)	<0.25%
Repeatability (resistance)	< .25%
Range of Cu film thickness	3 nm – 6,000nm
Types of measurable metal films	Cu, Ta, Al, Ti, TiN, W, Mo, Co, Ni, Ru, Cr
Measurement time per wafer	< 2 sec

*49-81 spots measurement for 200 mm wafers; 49-127 spots measurement for 300 mm wafers

*Optionally ACS-300 could be equipped with X-Y stage with 30,000+ spots measurement per wafer

Sample measurement of 200 mm Si wafer with 10 nm Cu film measured at 49 spots instantaneously



1040 Di Giulio Ave., Suite 200
 Santa Clara, CA 95050
 Tel: (408) 748-8787
 Fax: (408) 748-8687
www.MultiMetrix.com